Ain Shams University University College for Girls **Physics Department**

STUDY OF SOME OPTICAL AND STRUCTURAL PROPERTIES FOR ZINC SULFIDE THIN FILMS

PREPARED BY SPRAY PYROLYSIS ...

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ABSTRACT

Zinc sulfide is a transparent semiconductor with a wide band gap of about 3.6 - 3.7 eV. ZnS thin films are extensively used in industry for various purposes such as filters, photoelectric cells, etc...

In the present work, the spray pyrolysis technique is used which has many advantages over the conventional technique used in thin film preparation. It is simple, easy to construct and operate, needs no vacuum and economic. It allows mass production of large area thin layer coating at low cost.

The purpose of this work is to present a basic study of the spray deposition technique with regard to ZnS coatings, significant variables are the substrate temperature, carrier gas flow rate, the deposition and dopant type and its concentration.

The dependence of structural, electrical and optical properties of pure and incorporated cadmium zinc sulfide thin films deposited on glass substrate will be correlated with the spray parameter.

SUMMERY

In the peresent work structural, electrical and optical properties of pure and incorporated cadmium zinc sulfide thin Films deposited on glass substrate have been investigated.

Zinc sulfide is a semiconductor with a wide band gap of about 3.6-3.7 eV which makes it suitables as transparent material in the visible region. ZnS thin films are extensively used in industry for various proposes such as filters, photoelectric cells, etc.

Zinc sulfide in corporated cadmium to form ternary compounds $(0 \le x \le 1)$ are of considerable interest, for example, in hetrojunction solar cells.

It has been shown that the low efficiency of a CdS / Cu_yS (y ≥ 1.996 for chalcosite) solar cell might be due to the mismatching of lattice constants and electron affinities of the two components. A detailed model of CdS / Cu₂S solar cell heterojunction has been demonstrated to examine the design limit of this material combination cells. The results indicated that the attainable conversion efficiency of CdS / Cu₂S solar cell is roughly 10%, as compared to a theoritical limit of 16%, if no losses occured. A similar analysis of a cell using Cd ZnS inplace of CdS, yields an attainable efficiency of 15% and a theoretical efficieny of over 26%.

Also, the use of Zn CdS in place of CdS should permit greater open-circuit voltage and short circuit current.

The films were prepared by using a non-conventional preparation technique. It is called spray pyrolysis technique. It permit deposition on either insulating or conducting substrates

with a high degree of control over both the dimensions of the coating and their physical properties.

The use of spray pyrolysis techniques, has many advantages over the conventional techniques used in thin film preparation. It is simple, easy to construct and operation, needs no vacuum and economic. It allows mass production of large area thin layer coatings at low cost.

In the present work, zinc cadmium sulfide thin films are prepared by spraying a solution with any particular composition by mixing a convenient Cd and Zn salt solutions with a right proportion prior to spray. Therefore, no Zn gradient is expected to be along the substrate or perpendicular to it since all the spray droplets, which deposit on the substrate leading to the formation of the alloy films by pyrolytic decomposition have the same Cd: Zn ratio.

The prepared film is controlled by many parameters such as: substrate temperature deposition time, solution concentration, gas and solution flow rates and doping material. These parameters influence the structural, optical and electrical properties of the prepared ZnS films.

Therefore, much experiments were done to get the proper conditions such as gas and solution flow rates, the distance between the nozzle and substrate and the solution concentration for pure ZnS films which give a homogeneous and good appearence films. These conditions are kept constant all over the work.

A matrix of substrate tempertures ranging from 573-773 K° and spray time ranging from 10-60 minutes was made to obtain pure and incorporated cadmuim with different concentration zinc surfide thin solid Films.